

Electron beam evaporator pellets	Note
Al Cr Cu Ni Ti	For Lesker EBE1 and EBE2 tools
Etchants	Note
Al etchant Buffered oxide etchant 7:1 (BoE) Cr etchant Cu etchant	https://www.alfa.com/en/catalog/044581/ https://www.alfa.com/en/catalog/044582/ https://www.alfa.com/en/catalog/044583/
Liquid chemicals	Note
Acetone Hydrochloric acid (HCl) Hydrofluoric acid 49% (HF) Hydrogen peroxide 30% Isopropyl alcohol (IPA) Methanol Nanostrip Sulfuric acid (H2SO4)	
Photoresists	Note
HMDS adhesion promoter AZ P4620 LOR 3A AZ nLOF 2020 Shipley 1818 950 PMMA A4 494 PMMA A4 PGMEA	For DRIE For Suss and EVG 610 mask aligners For electron beam lithography For electron beam lithography
Nanoscribe resins	Note
IP-Visio Photoresist IP-Q Photoresist IP-Dip Photoresist IP-L Photoresist IP-S Photoresist	
Lithography developers and strippers	Note
TMAH 25% in water EBR-10A developer SU-8 developer AZ 400T stripper AZ developer 1:1 AZ 300 MIF developer AZ 726 MIF developer	

AZ 400K (1:4) developer MIBK/IPA developer MIF-319 developer KAM Remover PG	
Sputter Targets	Note
Au	For Cressington sputter coater
Al	For Lesker PVD75 DC tool
Cr	
Cu	
Ni	
Ti	
SiO2	For Lesker PVD75 RF tool
Al	For Clustex
Al2O3	
Cu	
Er2O5	
Hf	
HfO2	
Ir	
NbO2	
Nb2O5	
Pt	
Si	
Ta	
Ti	
TiN	
TiO2	
Ru	
V2O5	
VO2	
W	